

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

September 25, 2003

Applicants : Bruce W. Warnes, et al.

For : CHEMICAL VAPOR DEPOSITION APPARATUS AND METHOD

Serial No. : 09/950 013 Group: 1762

Filed : Sept. 10, 2001 Examiner: Meeks

Confirmation No. 9221

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

RESPONSE TO OFFICE ACTION

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OCT 0 8 2003

Dear Sir:

TC 1700

Please amend the above application as follows:

IN THE CLAIMS

1-18. (Canceled)

- 19. (Currently amended) A method of chemical vapor deposition, comprising flowing coating gas into in a preheat conduit disposed in and along a length of a heated coating chamber along a length thereof, heating said coating gas as it flows through said preheat conduit, and discharging the preheated coating gas into a gas distribution conduit in said coating chamber, and discharging the coating gas from the gas distribution conduit through a plurality of gas discharge openings at an opposing manifold wall having a plurality of gas flow openings out of alignment with said gas discharge openings such that there is no line-of-sight gas flow path from said gas distributon openings to said gas flow openings.
- 20. (Original) The method of claim 19 including heating said coating chamber by disposing it in a heated retort.
- 21. (Currently amended) The method of claim 19 including discharging the preheated coating gas at a lower end of said <u>preheat</u> conduit to the gas distribution conduit.